

Tool Configuration sheet

QAB30

1. GENERAL INFORMATION

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|------------------|--|
| | Ion sputter |
| Tool ID | QAB30 |
| Serial Number | 0429-001 |
| Vintage | 1996 |
| OEM | Hitachi High-Technologies Corporation. |
| Model | E-1030 |
| Process | Conductive film coating for SEM sample preparation |
| Software Version | Nothing |

2. SAMPLE SPECIFICATION

| | |
|----------------|--|
| Sample Size | Maximum sample diameter : 55mm Maximum sample height : 20mm |
| Sample Shape | Piece |
| Cassette Port | Nothing |
| Wafer Cassette | Nothing |
| SMIF Interface | Nothing |

3. SYSTEM CONFIGURATION

| | |
|---------------------------|--|
| | Type : Diode discharge magnetron type (electric field perpendicular to magnetic field) |
| | Electrode form : Opposed parallel disk (magnet embedded) |
| Spec.(Based on a catalog) | Voltage : 0.4kV DC |
| | Current : 0~35mA |
| | Target : Pt-Pd |
| | Maximum coating rate : 7.5nm/min |
| Options | Nothing |
| Pump | Rotary Pump |

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